

FORM PTO-1449  
(Modified)U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.:  
FIS920000191U51

SERIAL NO.:

INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT

APPLICANT: Christopher P. Ausschnitt

(Use several sheets if necessary)  
(37 CFR 1.98(b))

FILING DATE:

GROUP:

10974 U.S. PTO  
09/165148

## REFERENCE DESIGNATION

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
<i>DBE</i>	AA	5,629,772	5/13/97	Ausschnitt			
<i>DBE</i>	AB	5,712,707	1/27/98	Ausschnitt et al.			
<i>DBE</i>	AC	5,731,877	3/24/98	Ausschnitt			
<i>DBE</i>	AD	5,756,242	5/26/98	Koizumi et al.			
<i>DBE</i>	AE	5,757,507	5/26/98	Ausschnitt et al.			
<i>DBE</i>	AF	5,776,645	7/7/98	Barr et al.			
<i>DBE</i>	AG	5,805,290	9/8/98	Ausschnitt et al.			
<i>DBE</i>	AH	5,914,784	6/22/99	Ausschnitt et al.			
<i>DBE</i>	AI	5,928,822	7/27/99	Rhyu			
<i>DBE</i>	AJ	5,949,547	9/7/99	Tseng et al.			
<i>DBE</i>	AK	5,953,128	9/14/99	Ausschnitt et al.			

## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY OR PATENT OFFICE	CLASS	SUB- CLASS	TRANSLATION	
							YES	NO
	AL							
	AM							
	AN							
	AO							
	AP							

## OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)

<i>DBE</i>	AQ	Intellectual Property Network, <i>Method for Measuring Semiconductor Lithographic Tool Focus and Exposure</i> , IBM Technical Disclosure Bulletin, July 1987, pages 516-518.
<i>DBE</i>	AR	Alexander Starikov, <i>Exposure Monitor Structure</i> SPIE Integrated Circuit Metrology, Inspection, and Process Control IV, Vol 1261, 1990, pages 315-324
	AS	

EXAMINER

DATE CONSIDERED

*DBE**5/16/03*

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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<b>FORM PTO-1449</b> (Modified)  <b>U.S. DEPARTMENT OF COMMERCE</b> <b>PATENT AND TRADEMARK OFFICE</b>  <b>INFORMATION DISCLOSURE</b> <b>STATEMENT BY APPLICANT</b>  (Use several sheets if necessary) (37 CFR 1.98(b))	<b>ATTY. DOCKET NO.:</b> FIS920000191US1	<b>SERIAL NO.:</b>
	<b>APPLICANT:</b> Christopher P. Ausschnitt	
	<b>FILING DATE:</b>	<b>GROUP:</b>


REFERENCE DESIGNATION		U.S. PATENT DOCUMENTS					
EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUB-CLASS	FILING DATE IF APPROPRIATE
<del>DBE</del>	AT	5,965,309	10/12/99	Ausschnitt et al.			
<del>DBE</del>	AU	5,968,693	10/19/99	Adams			
<del>DBE</del>	AV	5,976,740	11/2/99	Ausschnitt et al.			
<del>DBE</del>	AW	5,981,119	11/9/99	Adams			
<del>DBE</del>	AX	5,985,495	11/16/99	Okumura et al.			
<del>DBE</del>	AY	6,004,706	12/21/99	Ausschnitt et al.			
<del>DBE</del>	AZ	6,027,842	2/22/00	Ausschnitt et al.			
<del>DBE</del>	BA	6,128,089	10/3/00	Ausschnitt et al.			
<del>DBE</del>	BB	6,130,750	10/10/00	Ausschnitt et al.			
<del>DBE</del>	BC	6,137,578	10/24/00	Ausschnitt			
	BD						

**FOREIGN PATENT DOCUMENTS**

		DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY OR PATENT OFFICE	CLASS	SUB-CLASS	TRANSLATION	
							YES	NO
	BE							
	BF							
	BG							
	BH							
	BI							

**OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)**

	BJ	
	BK	
	BL	

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